



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. ....09/536,037  
Filing Date .....March 27, 2000  
Inventor ..... Weimin (Michael) Li et al.  
Assignee .....Micron Technology, Inc.  
Group Art Unit .....2822  
Examiner .....Toniae M. Thomas  
Attorney's Docket No. ....MI22-1398  
Customer No.....021567  
Title: Low k Interlevel Dielectric Layer Fabrication Methods

To: Box RCE  
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**SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT**

**References -- See Attached Form PTO-1449**

This Request for Continued Examination (RCE) Application is being filed in an abundance of caution to ensure consideration of the references listed on the attached form PTO-1449.

The attached form PTO-1449 is submitted in compliance with 37 CFR §1.56. No admission is made regarding whether the submitted references are prior art.

Respectfully submitted,

Dated: 11 May 2005

By: James E. Lake  
James E. Lake  
Reg. No. 44,854

**EV549570593**

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-1398	SERIAL NO. 09/536,037		
<div style="display: flex; align-items: center;"> <div> <p>LIST OF ART CITED BY APPLICANT</p> <p>(Use several sheets if necessary)</p> </div> </div>				APPLICANT: Li et al.			
				FILING DATE March 27, 2000	GROUP 2822		
U.S. PATENT DOCUMENTS							
*Examiner's Initials		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	6,121,133	09/19/00	Iyer et al.	438	636	
	AB	6,632,712 B1	07/11/00	Ang et al.	438	212	
	AC	5,711,987	07/05/88	Bearinger et al.	427	7	
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	<div style="display: flex; justify-content: space-between; border-bottom: 1px solid black; padding-bottom: 2px;"> <span>Translation</span> </div> <div style="display: flex; justify-content: space-between; padding-top: 2px;"> <span>Yes</span> <span>No</span> </div>
	AJ	TW 47112 A	01/01/2002	Taiwan – Abstract			X
	AK						
	AL						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
	AM		Wolf, S., and Tauber, Richard, Silicon Processing for the VLSI Era; Vol. 1; Process Technology; "Silicon: Single Crystal Growth and Wafer Preparation"; pages 1 and 2				
	AN						
EXAMINER		DATE CONSIDERED					
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>							

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